

Fabrication of Graphene/Bi₂Se₃/Graphene heterostructure without the surface oxidation of Bi₂Se₃

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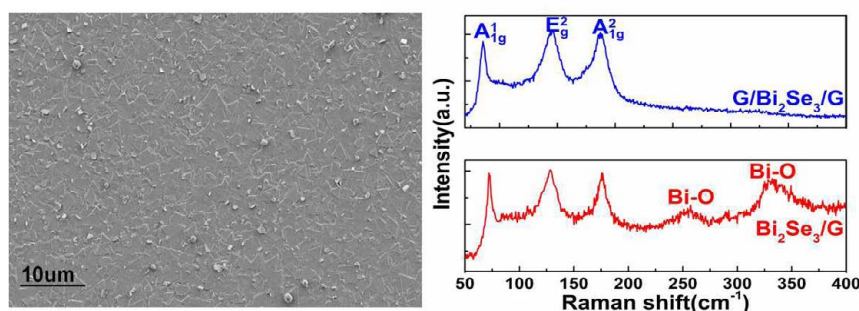
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Abstract

Graphene/Bi₂Se₃/Graphene (G/Bi₂Se₃/G) sandwich hybrids were fabricated via chemical vapor deposition. The medium graphene layer is used to synthesize the high-quality Bi₂Se₃, benefiting from the smaller lattice mismatch between graphene and Bi₂Se₃. The covering graphene layer is designed to inhibit the surface oxidation of Bi₂Se₃ layers which are easily changed to BiO_x in the atmosphere. The Raman spectroscopy, scanning electron microscopy and X-ray diffraction confirm the high-quality and uniform Bi₂Se₃ film. The Raman spectroscopy and X-ray diffraction investigates antioxidant ability of the G/Bi₂Se₃/G structure. We conclude that the graphene can effectively improve the crystal quality of Bi₂Se₃ and inhibit the surface oxidation of it.

Graphical abstract

The method to improve the crystal quality and inhibit the surface oxidation is important for the application of the Bi₂Se₃ films. Graphene/Bi₂Se₃/Graphene (G/Bi₂Se₃/G) sandwich hybrids were fabricated here *via* chemical vapor deposition. The medium graphene layer is used to synthesize the high-quality Bi₂Se₃, benefiting from the smaller lattice mismatch between graphene and Bi₂Se₃. The covering graphene layer is designed to inhibit the surface oxidation of Bi₂Se₃ layers which are easily changed to BiO_x in the atmosphere. We conclude that the graphene can effectively improve the crystal quality of Bi₂Se₃ and inhibit the surface oxidation of it.



Introduction

Bi₂Se₃, an ideal topological insulator (TI) with a single Dirac cone residing in a large bulk bandgap (~0.3 eV), has attracted extensive scientific interests to experimental and theoretical communities [1]. Layer-structured Bi₂Se₃ materials may be applied for the future spintronics and quantum computing devices due to large ratio of surface-to-volume, thus it is urgent to synthesize high-quality Bi₂Se₃ with defined sizes [2-4]. Various methods have been tried to fabricate Bi₂Se₃ thin film, such as molecular beam epitaxial (MBE) [5,6], solvothermal synthesis [7], mechanical exfoliation [8], metal-organic chemical vapor deposition (MOCVD) [9] and chemical vapor deposition (CVD) [10-13]. Compared with other methods, CVD is an inexpensive and effective strategy to obtain Bi₂Se₃ materials. Directly fabricated the large-area high-quality Bi₂Se₃ film on SiO₂ is difficult due to the larger lattice mismatch between Bi₂Se₃ and SiO₂. Graphene film, a 2-D atomic-scale honeycomb lattice made of carbon atoms, can be used to fabricate the high-quality epitaxial layer benefiting from that the van der Waals interactions between epitaxial layer and graphene

can efficiently suppress the negative effects of the lattice mismatch [12]. Here, we fabricated large-area high-quality Bi₂Se₃ thin film in a Se-rich environment via a catalyst-free CVD method on the graphene/SiO₂ substrate.

However, the synthesized Bi₂Se₃ thin film gets doped after being exposed to the atmosphere and the content of BiO_x increased with the increase of the exposed time. Such rapid surface oxidation reduces the relative contribution of surface states, which greatly limits the development of the Bi₂Se₃ devices [14]. Therefore, a method to inhibit the surface oxidation is urgently required. Graphene is capable of

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both scavenging free-radicals [15-18] and can serving as gas barriers [19-23], these dual effects make graphene be effective in improving oxidation stability of Bi₂Se₃. In this study, we fabricated high-quality G-Bi₂Se₃-G heterostructure via CVD. There are two advantages of this heterostructure: (1) the 2D growth single-crystal Bi₂Se₃ thin film can be successfully deposited on the graphene film; (2) the oxidation process of the Bi₂Se₃ is significantly delayed compared with that without the protection of the graphene.

Experimental method

The monolayer graphene film was synthesized on the Cu foil via a CVD method and immediately transferred to the SiO₂ substrate using wet-etching process. Bi₂Se₃ thin film was grown on the monolayer graphene substrate along the lateral direction with the help of Se powder in the source materials via CVD method in a horizontal quartz tube (~3.5 inch in diameter), which has been investigated by our previous work [13]. As shown in Figure 1, high purity powder of Bi₂Se₃ and Se as the precursor for evaporation was located in the constant-temperature zone and the G/SiO₂ substrate was placed on a quartz boat in the down-stream zone. The horizontal quartz tube was pumped to 1.0×10⁻⁶ Torr by mechanical pump and aerated Ar gas with ~50 sccm flow rate to remove any oxygen residue. The constant- temperature zone of the furnace was heated and maintained at 550°C for 15 min. The furnace was naturally cooled down to the ambient temperature with the Ar gas flowing (~50 sccm). The fabricated Bi₂Se₃/G is immediately covered by another graphene layer to get the G/Bi₂Se₃/G sandwich hybrid structure. Following the fabrication, the morphology, chemical analysis, structural properties and single-crystalline structure of the G/Bi₂Se₃/G were characterized by scanning electron microscopy (SEM), energy dispersive X-ray spectroscopy (EDS), Raman spectroscopy and X-ray diffraction (XRD).

Results and discussion

Graphene layer plays a vital role in forming uniform Bi₂Se₃ thin film. Figure 2a exhibits the SEM image of the Bi₂Se₃ deposited on the SiO₂ substrates with and without the graphene film. From the right of the Figure 2a, only Bi₂Se₃ nanoplates were obtained in the case of no graphene serving as medium layer, which can be easily observed from SEM image under a high magnification (shown in the Figure 2b). As can be seen, the Bi₂Se₃ nanoplates grow along the lateral direction with the help of the Se powder in the source materials serving as growing point. However, the large lattice mismatch with SiO₂ substrates makes it impossible to form Bi₂Se₃ film. Large area high-quality Bi₂Se₃ thin film was synthesized on the graphene/SiO₂ on the left of the images, which benefits from the van der Waals interactions between the graphene and Bi₂Se₃ layer. Figure 2c shows the SEM images of Bi₂Se₃ samples grown on SiO₂ substrate with the graphene layer under 10× magnificant, symmetric triangular and hexagonal morphologies with a smooth multi-layered structure aligned in the same orientation. Individual Bi₂Se₃ plates deviated from the main orientation may be introduced by the lattice mismatch or defects of the graphene substrate. The EDX spectrum of the samples displayed in Figure 2d shows that the

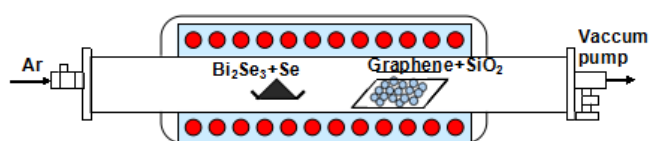


Figure 1. Schematic of the hot-wall CVD system used in this study.

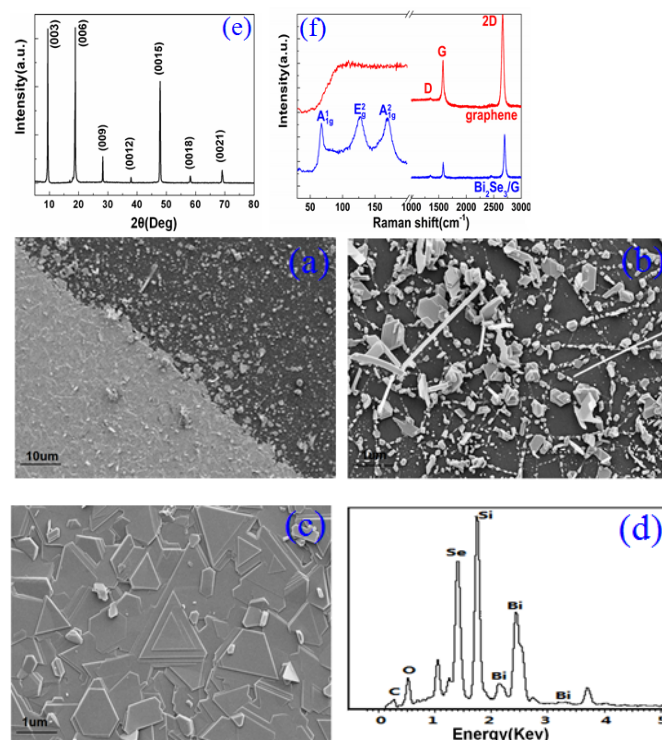


Figure 2. (a) The SEM image of the Bi₂Se₃ deposited on the SiO₂ substrates with and without the graphene film. (b) High magnification SEM image of Bi₂Se₃ nanoplates grown on the SiO₂ substrate. (c) High magnification SEM image of the Bi₂Se₃ thin film deposited on the G/SiO₂ substrate. (d) EDX spectrum of the Bi₂Se₃/G hybrid materials. (e) 2θ-ω X-ray diffraction pattern of the prepared sample. (f) The Raman spectra of the graphene and Bi₂Se₃/G.

Table 1. Quantitative atomic analysis of the Bi and Se elements.

Element	Weight%	Atomic%
C	0.39	2.68
O	10.53	34.02
Si	20.78	38.24
Se	22.52	14.7 4
Bi	45.77	10.3 2
Total	100.0	

energy signal peak of Se and Bi are detected on the G/SiO₂ substrate. Table 1 provides that atomic ratio of Se and Bi is nearly equal to the stoichiometric ratio of 1.5 for Bi₂Se₃, concluding that we have produced Bi₂Se₃ thin film with uniform chemical composition.

It is possible to verify the crystal structure of the Bi₂Se₃ thin film by XRD measurement. As shown in Figure 2e, only (003) family peak including (003), (006), (009), (0012), (0015), (0018) and (0021) are detected, proving that the sample has a good c-axis orientation and periodic. FWHM of lattice diffraction peaks is less than 0.03 [24], indicating a high quality of the Bi₂Se₃ single crystal.

In order to give a more definite identification of crystal quality of Bi₂Se₃ single crystal, Raman spectroscopy were carried out at room temperature. The typical Raman spectra of the graphene and Bi₂Se₃/G on the SiO₂ substrate are simultaneously shown in Figure 2f. In the low frequency region, the spectrum of the graphene is rising, which may be

related with the SiO₂ substrates. The spectrum of the Bi₂Se₃ reveals three characteristic bands of the Bi₂Se₃ thin film: ~72, ~131 and ~174 cm⁻¹ respectively correspond to the A_{1g}^1 , E_g^2 and A_{1g}^2 vibrational modes [25]. The symmetric Lorentzian line shape of all of the Raman peaks means that the Bi₂Se₃ thin film samples have a crystal structure. Obvious G and 2D bands at ~1585 and ~2700 cm⁻¹ representing for graphene film, were also detected in the high frequency region. The intensity ratio of the 2D peak to G peak was measured to be around 2.0, which are typical signatures of a monolayer graphene film. In addition, after the deposition of the Bi₂Se₃ thin film, the 2D band of the monolayer graphene film becomes broader and up shifts by ~28 cm⁻¹, which probably be attributed to the van der Waals interaction of the Bi₂Se₃ thin film and graphene. These features imply the fact that the graphene film still possesses perfect structural properties after the deposition of the Bi₂Se₃ thin film.

Quintuple layer (QL) in Bi₂Se₃ is ordered in a Se–Bi–Se–Bi–Se sequence via covalent bond and adjacent layer are connected by weak van der Waals force. Dangling bonds appeared in the surface of Bi₂Se₃ film as a result of the Se vacancies make Bi₂Se₃ easily react with oxygen atoms of environment and form BiO_x [11,14], which great limit the application of Bi₂Se₃. The stability of the Bi₂Se₃ sample as a function of exposure time in air as shown in Figure 3a, the Raman modes at 72 cm⁻¹, 131 cm⁻¹, 174 cm⁻¹ attributed to Bi₂Se₃ are clearly seen. However, the modes of BiO_x at 250 cm⁻¹ and 328 cm⁻¹ [26] appears when the sample is left in air over ten days. To further demonstrate the formation of BiO_x, XRD measurement was carried out as shown in Figure 3b, the diffraction peaks of BiO_x at 2θ = 27.377, 40.053 and 41.884 appears respectively [11], which correspond well with the Raman spectrum (shown in Figure 3a). It illustrates that the formation of BiO_x is very fast.

In order to delay the oxidation of Bi₂Se₃ film, we transfer a covering graphene on it again to fabricate a G/Bi₂Se₃/G sandwich Dirac heterostructure. The covering graphene can be mixed with Bi₂Se₃ thin film at a molecular level to maximize the contact between them by the van der Waals interaction [22]. The monolayer graphene are stable under ambient conditions and its pore size is far less than the size of oxygen molecules, which make it a perfect gas barrier. In addition, it is capable of scavenging free-radicals, thus the covering graphene layer can effectively delay the process of surface oxidation of Bi₂Se₃ [23]. The Raman spectrum signal of the G/Bi₂Se₃/G sample shown in Figure 4a is different from the Raman spectra changes of the Bi₂Se₃/G sample and remains unchanged continuously. It provides us a definite experimental evidence that the covering graphene can effectively delay the surface oxidation of Bi₂Se₃.

We carried out a 10 × 10 μm² Raman A_{1g}^1 , E_g^2 and A_{1g}^2 band mappings of the G/Bi₂Se₃/G sample to prove the chemical stability of it. As we

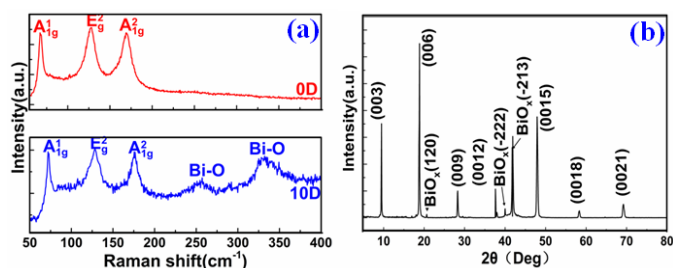


Figure 3. (a) The Raman spectrum of the Bi₂Se₃/G sample respectively exposed in air for 0 day and 10 days. (b) 2θ–ω X-ray diffraction pattern of the Bi₂Se₃/G sample exposed in air.

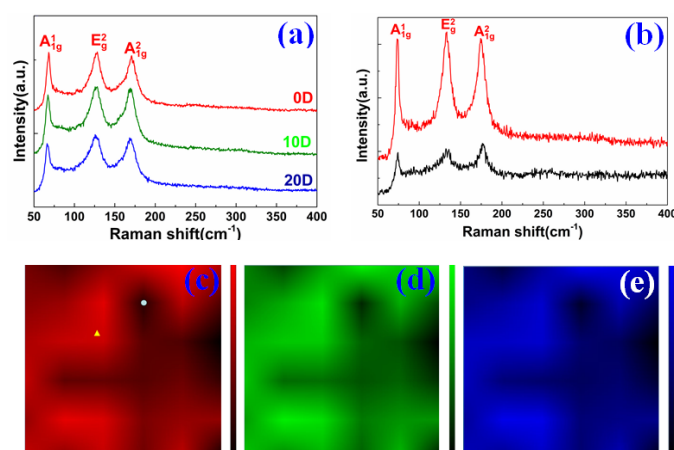


Figure 4. (a) The Raman spectrum of the G/Bi₂Se₃/G sample exposed in air for different days. (b) Raman spectrum respectively from the point marked in (c) by the yellow triangle (red) and white dot (black). (c)–(e) The scanning Raman A_{1g}^1 , E_g^2 and A_{1g}^2 band mappings of the G/Bi₂Se₃/G sample, respectively.

all known, the intensity of the out-of-plane vibrational mode, A_{1g}^1 and A_{1g}^2 peak, is more sensitive to the thickness [25]. The thickness of the G/Bi₂Se₃/G films can be identified by the Raman band mappings with the different color. As can be seen from Figure 4c, 4d and 4e, relatively smooth A_{1g}^1 , E_g^2 and A_{1g}^2 band mappings of Bi₂Se₃ thin film with uniform colour are formed, indicating the large-area layer-controlled Bi₂Se₃ thin film. In Figure 4b, the red spectrum is taken from the red region marked by the yellow triangle in Figure 4c. It presents the typical characteristics of the smooth Bi₂Se₃ film: obvious bands A_{1g}^1 , E_g^2 and A_{1g}^2 at ~72, ~131 and ~174 cm⁻¹. As can be seen, the intensity of A_{1g}^1 and A_{1g}^2 peak is lower than that of E_g^2 peak (in-plane mode), which is the representative of high quality and uniform Bi₂Se₃ thin film with stable chemical properties. The black region of the band mapping is formed due to the different thickness of the prepared Bi₂Se₃ thin film, which still features a micro-scale inhomogeneity structure. The black spectrum in Figure 4b is obtained from the black region in Figure 4(c), which is marked by the white dot. The intensity of A_{1g}^1 and A_{1g}^2 is stronger than that of E_g^2 , describing the thicker layer of Bi₂Se₃ are formed, well corresponding with the band mapping of the sample. The mode of BiO_x (250 cm⁻¹ and 328 cm⁻¹) can't be obtained consistently, concluding that the covering graphene layer is an effective packaging material to inhibit the oxidation process of Bi₂Se₃ under ambient conditions.

Conclusion

In conclusion, we have demonstrated that high-quality and uniform Bi₂Se₃ thin film can be obtained with graphene serving as medium layers and the covering graphene can effectively delay the process of surface oxidation of Bi₂Se₃. This method presents a simple and economical technique to fabricate Bi₂Se₃ film with chemistry stable under ambient conditions. It presents a practical help for probing topological insulator surface state by transport measurements and pave the way for applying in the spintronics and quantum computing.

Acknowledgments

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